



**Fabrication and Verification of a Glass-Silicon-Glass Micro-/nanofluidic Model for Investigating Multi-phase Flow in Shale-like Unconventional Dual-Porosity Tight Porous Media**

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## 45 **Abstract**

46 Unconventional shale or tight oil/gas reservoirs that have micro-/nano sizes of the dual-scale  
47 matrix pore throats with micro-fractures may result in different fluid flow mechanisms  
48 compared with conventional oil/gas reservoirs. Microfluidic model, as a potential powerful tool,  
49 has been used for decades for investigating fluid flow at pore-scale in energy field. However,  
50 almost all microfluidic models were fabricated by using etching methods and rare ones were  
51 having dual-scale micro-/nanofluidic channels. Herein, we developed a lab-based, quick-  
52 processing and cost-effective fabrication method using lift-off process combined with anodic  
53 bonding method, which opts out of using any etching methods. A dual-porosity matrix/micro-  
54 fracture pattern, which can mimic the topology of the shale with random non-regularly grain  
55 shapes was designed by Voronoi algorithm. The pore channel width range is 3  $\mu\text{m}$  to 10  $\mu\text{m}$  for  
56 matrices and 100-200  $\mu\text{m}$  for micro-fractures. Silicon is used as the material to evaporate and  
57 deposit onto the glass wafer and then bonded with another glass wafer. The channel depth is  
58 the same 250 nm to the deposited silicon thickness. By using the advanced confocal laser  
59 scanning microscopy system (CLSM), we directly visualized the pore level flow within micro-  
60 /nano dual-scale channels with fluorescent-dyed water and oil phases. We found serious  
61 fingering phenomenon when water displacing oil in the conduits even the water has higher  
62 viscosity and the residual oil distributed as different forms in the matrices, micro-fractures and  
63 conduits. We demonstrated that different matrix/micro-fracture/macro-fracture geometries  
64 would cause different flow patterns that affect the oil recovery consequently. Taking advantage  
65 of such a micro-/nano dual-scale 'shale-like' microfluidic model fabricated by a much simpler  
66 and lower-cost method, studies on complex fluid flow behavior within the shale or other tight  
67 heterogeneous porous media would be benefited significantly.

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## 70 **1. Introduction**

71 Unconventional reservoirs, including shales and other types of tight formations, which  
72 intrinsically have much lower permeability than conventional reservoirs with micro-/nano scale  
73 dual-porosity features, can exhibit highly varying properties within microscopic confinement.  
74 Therefore, microfluidic model, as a powerful pore-scale level approach is needed to better  
75 understand the flow behavior and mechanism within the heterogeneous porous media of the  
76 shale-like tight oil/gas reservoirs. According to the average pore-throat diameter size of  
77 unconventional shale and other tight oil/gas reservoirs, the ratio of pore surface area to the pore  
78 volume which can be  $50 \times 10^4 \text{ cm}^{-1}$  (approximately 700 if represented by the ratio of channel  
79 width to depth in a microfluidic model), is much larger than that of conventional porous media  
80 which can be  $1.8 \times 10^{-4} \text{ cm}^{-1}$  (approximately 16 if represented by the ratio of channel width to  
81 depth in a microfluidic model)<sup>1, 2</sup>. Hence, the hypothesized surface interfacial phenomena  
82 dominated fluid flow make the liquid and gas transportation through shale are still uncertain.<sup>3</sup>  
83 Although some of microfluidic devices possessing dual-scale matrix/fractures network features  
84 have been built by using different fabricating method,<sup>4-7</sup> the channels are all in micro scale for  
85 any dimensions and not having large width-to-depth ratio (2-26), which cannot representing  
86 fluid pathways of shale or tight dual-scale reservoirs. Until recently, though the first micro-  
87 /nano PDMS-glass and quartz-glass dual-scale microfluidic models come up to represent dual  
88 scale shale,<sup>8</sup> the width-to-depth ratio (1-25) still stay small. Besides, the fabrication method  
89 cannot guarantees oil flow on PDMS-glass model and high-pressure experiments on glass-glass  
90 model due to the bonding issue.

91 Although PDMS micromodel now can realize sub-100 nm dimensions,<sup>8, 9</sup> it is still not a  
92 proper candidate for conducting experiments involving organic nonpolar fluids,<sup>10</sup> which is  
93 ubiquitous in many petroleum and environmental scenarios.<sup>11-14</sup> Hence, nonorganic materials  
94 based silicon-glass or glass-glass microfluidic models have risen in response and widely been

95 used to fabricate micro-/nanofluidic models capable of handling harsh physical and chemical  
96 conditions for energy fields.<sup>15-19</sup> For silicon-glass ones, since silicon has no transparency to  
97 visible light, a glass wafer is always being a transparent cover plate anodic bonded over the  
98 silicon substrate to make it possible for direct observation under a microscope.<sup>20-22</sup> To achieve  
99 fully transparency and for the superiorities of compatibility with many solvents,<sup>23, 24</sup> high  
100 stiffness for handling high pressure fluid flow experiments<sup>25-27</sup> and the easiness of surface  
101 wettability alteration by different methods,<sup>28, 29</sup> the glass itself has long been a preferred  
102 microfluidic model substrate. The choice between the two is mainly depending on the goals and  
103 needs. Silicon substrate would be chosen when one needs more precise channel sizes and  
104 straight channel side walls when using dry etching method.<sup>30</sup> Although glass substrates can also  
105 be dry-etched,<sup>31, 32</sup> the low etching rate, low etching selectivity and high facility cost make wet  
106 etching a more popular way, which make use of buffered hydrofluoric acid or mixtures of acids  
107 as the etchant solutions to etch channels on glass substrates.<sup>33-35</sup> The main drawback is that the  
108 isotropic wet etching process cannot reach perfect vertical walls,<sup>33</sup> yet this imperfect trapezoidal  
109 shape can be leveraged to generate a 2.5 D micromodel by controlling the etching depths of two  
110 neighboring pores.<sup>36</sup> Other fabrications of semi or fully transparent microfluidic models for  
111 energy and other fields can be found elsewhere in details.<sup>37-42</sup>

112 Among all available fabrication methods, thin film deposition, as a fast, low cost and  
113 simple process, has been used to produce micro-/nanochannels in several applications.<sup>43-45</sup>  
114 However, for energy field microfluidic system, it is rarely used and only as an auxiliary method  
115 to deposit a protection layer and hard mask for subsequent wet etching or dry etching process.<sup>8,</sup>  
116 <sup>46, 47</sup> The aforementioned glass-quartz transparent micro-/nanofluidic devices that emulates dual-  
117 scale properties of shale and tight-oil reservoirs also utilized the thin film deposition to help  
118 make the model.<sup>8</sup> They used thermal deposition to coat Cu film onto a lacey carbon support  
119 film and reactive ion etched the quartz substrate based on the mask. Finally, two glass wafers  
120 were bonded by continuously flushing demineralized water between the two wafers and

121 combining them stand for more than 3 hours.<sup>48</sup> However, the reactive ion etching method can  
122 produce etching byproducts that would clog the thinner channels and the ‘sag’ of the lacey  
123 carbon film is very likely occurred across larger apertures. Besides, it needs at least 3 to 4 days  
124 standing time for two plates bonded at least 80% strength, which is  $61.8 \pm 2.6 \text{ N/cm}^2$ , to use  
125 for a fluid flow experiment. Although this bonding method can be realized at room temperature  
126 to avoid deformation of glasses at high temperature by using fusion bonding, the bonding  
127 strength and temperature resistance are questionable.

128 How to fabricate a ‘shale-like’ micro-/nanofluidic model that has a large width-to-depth  
129 ratio (12-2000) in a time-efficient and cost-effective way and meanwhile, keeping it fully  
130 transparent and strong bonding strength remains challengeable and needful these days. In this  
131 work, we, for the first time, deliver such a possibility by using the direct lift-off process  
132 combined with the anodic bonding process. For glass-based models, both wet etching and dry  
133 etching need to deposit a metal layer at first step and then do the etching at second step. The  
134 lift-off process and the etching process on a glass substrate both require the photolithography  
135 pattern and thin film deposition<sup>49</sup>. Therefore, instead of using any etching methods downwards  
136 the substrate, we build the grains upwards and use them directly as the intermediate layer for  
137 anodic bonding. By skipping the etching process, one may save more than 5 hours a day for  
138 fabricating 20 samples (2 cm × 2 cm) excluding other preparation times for etching. This simple,  
139 time-saving and cost-effective method improves the efficiency of fabricating a micro-  
140 /nanofluidic model significantly. The detailed fabrication processes are presented in the  
141 following sections. Finally, the functionality and practicability of the micro-/nanofluidic model  
142 are demonstrated based on the multiphase fluid flow experimental results.

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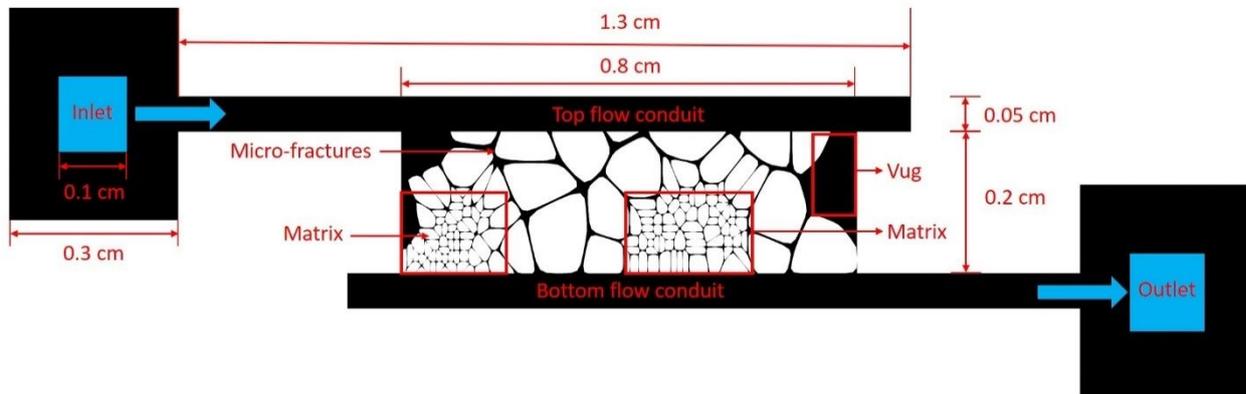
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## 146 **2. Results and discussion**

### 147 **2.1. Dual-porosity Pore Network Design**

148 To generate a complex heterogeneous porous media for investigating the multiphase flow  
149 with a microfluidic model, the Voronoi tessellation algorithm was utilized to mimic the real  
150 reservoir with random geometries and labyrinth-like pore networks.<sup>50</sup> The Voronoi diagram,  
151 also called Voronoi tessellation or Voronoi decomposition, is to use a computational geometry  
152 algorithm to partition a plane into different sizes of non-overlapping regions based on the  
153 closest distances among the randomly preset points on the plane<sup>51</sup>. However, simple Voronoi  
154 tessellation pattern with connected straight channels cannot represent the real ‘convergent-  
155 divergent’ conditions within the porous media and all the channels share the same width. Herein,  
156 we used the improved Voronoi tessellation algorithm in AutoCAD software to design a dual-  
157 porosity pattern with two matrixes and micro-fractures connected with the matrixes with  
158 different channel widths. Further, the grains were designed as close as possible to granular  
159 shapes rather than polygonal shapes to represent the real rock grains in reservoirs, which make  
160 the pore networks have the ‘convergent-divergent’ profiles. As shown in Figure 1, the porous  
161 media including two matrixes and micro-fractures is sandwiched between two flow conduits,  
162 which can be regarded as macro-fractures. The lengths of two flow conduits and the porous  
163 media are 1.3 cm and 0.8 cm and the widths are 0.05 cm and 0.2 cm. Connecting to the flow  
164 conduits that have side lengths 0.1 cm are the inlet and outlet for flow injection and recovery.  
165 The outer squares with 0.3 cm side length are the pre-saturation zone to decrease the probability  
166 of blocking when injecting and recovering the fluids. The intergranular channels within the  
167 matrixes are of narrowest ones from 3  $\mu\text{m}$  to 10  $\mu\text{m}$  and 100-200  $\mu\text{m}$  for the micro-fractures.  
168 Several vugs were also yielded by eliminating amount of grains at left and right side of the  
169 porous media. The porous media, excluding the flow conduits, consists of 192 grains with a

170 total porosity of 28%, which could be smaller if the vugs are not counted. The porosity for the  
 171 two matrixes is approximately 5% and 23% for combined micro-fractures and vugs.



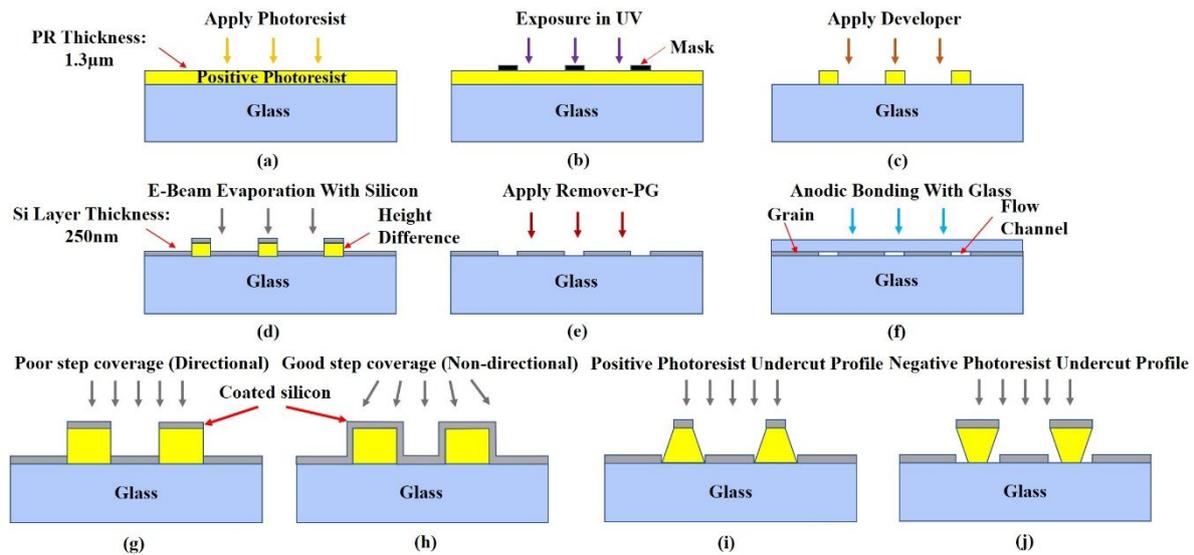
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173 Figure 1. Dual-porosity pattern design using Voronoi algorithm

174

## 175 2.2. Micromodel Fabrication

176 The micromodel was fabricated lab-based and the successive fabrication steps of the  
 177 micromodel are presented in Figure 2(a-f). A glass substrate was first spin-coated with the  
 178 S1813 positive photoresist and then the pattern was developed under UV exposure followed  
 179 with MF321 developer. The substrate was then loaded into a vacuum chamber and coated with  
 180 an amorphous silicon layer using e-beam evaporation at an average rate of  $1.6 \text{ \AA/s}$  at  
 181 temperatures  $16 - 50$  Celsius degree . Finally, lift-off process removed the photoresist in the  
 182 channels using remover-PG (a proprietary solvent stripper designed for efficient and complete  
 183 removal of photoresists). The glass substrate was anodic bonded with another glass wafer after  
 184 two holes were punched as inlet and outlet using UV laser. Contrast to the high cost and long  
 185 fabrication workflow with wet or dry etching process for a glass-based micromodel with  
 186 complex porous media patterns, this simple, fast and cost-effective fabricating method may  
 187 produce amounts of micro-/nanofluidic models in a short time period (average twenty samples  
 188 per day). Details of each fabrication process was discussed in the following sections.



189

190 Figure 2. Schematic workflow of micro-/nanofluidic model fabrication process: (a) photoresist  
 191 spin-coated on the glass substrate; (b) UV exposure to change the chemical properties of  
 192 uncovered photoresist; (c) developer applied to wash away exposed photoresist; (d) e-beam  
 193 evaporation used to deposit thin silicon later onto the glass substrate; (e) remover-PG used to  
 194 remove residual photoresist in the channels; (f) anodic bonded with another glass wafer on top;  
 195 (g)(h): illustration of deposition poor and good step coverage comparison; (i)(j): positive and  
 196 negative photoresist undercut profile comparison when coated on the substrate;

197

### 198 2.2.1. Materials

199 For fabricating one complete glass-silicon-glass micromodel, two glass wafers were used  
 200 as both the substrate and the cover-plate. The Schott Borofloat 33 Glass wafers are square  
 201 double side polished (University Wafer), with the side length of 5 cm and the thickness of  $500 \pm 20 \mu\text{m}$ . Silicon pellets (R.D. Mathis) were used as the evaporation material to be coated onto  
 202 the glass substrate to enable an easy anodic bonding process with glass since they have the  
 203 similar thermal coefficient of expansion. (For silicon is  $2.6 \times 10^{-6} /\text{K}$  and Borofloat 33 glass is  
 204  $3.25 \times 10^{-6} /\text{K}$  at  $20^\circ\text{C}$ ).

206

### 207 **2.2.2. Photolithography**

208 First, the glass substrate was first rinsed with acetone and methanol for two times to  
209 remove dust and oil, and then blow-dried completely using dry air. The Microposit S1813  
210 positive photoresist was spin coated uniformly onto the glass substrate at 4000 RPM for 40 s  
211 with the thickness of 1.3 microns. Then the substrate was softbaked on the hot plate at 115  
212 Celsius degrees for one minute to eliminate the moisture on the substrate. Later, the substrate  
213 was soft contact with the printed polymeric mask and exposed to UV400 ultra-violet (UV) light  
214 using Karl Suss MA6 aligner. The UV exposure time depends on the photo resist type. We used  
215 S1813 which requires 150mJ/cm<sup>2</sup>. The exposure power of our mask aligner is about 11mW/cm<sup>2</sup>  
216 so the exposure time is 10-15s for our samples. Lastly, the exposed photoresist was removed  
217 by soaking the substrate into the MF321 developer for 50 s until the pattern can be seen clearly  
218 and then rinsed using deionized (DI) water for thirty seconds. One substrate contains two  
219 patterns to save the space of the substrate.

### 220 **2.2.3. E-Beam Vapor Evaporation**

221 Choosing a proper evaporation method for depositing a thin silicon film on the glass  
222 substrate is of great importance throughout the whole work. Different from chemical vapor  
223 deposition method (CVD) that takes place at high temperatures, E-beam evaporation allows  
224 depositions at relatively low substrate temperature around 16-50 Celsius degrees while yielding  
225 a high deposition rate (1.6 Å/s at temperatures 16 - 50 Celsius degree) and has been used for  
226 micro-electro-mechanical systems (MEMS) for a long time.<sup>31, 52, 53</sup> The low deposition  
227 temperature prevents the deformation of the glass wafers at high temperatures around 550  
228 Celsius degrees. Thermal evaporation, being as another physical evaporation, may as well heat  
229 up the substrate to over 250-300 Celsius degree during deposition process.<sup>54</sup> Besides, chemical  
230 vapor deposition may generate gaseous or liquid byproducts which may lead to impurities on  
231 the substrate. Except for these two reasons in terms of deposition temperature and contaminants,  
232 the most important reason for choosing e-beam physical evaporation is the consideration of the

233 poor step coverage of deposited film as shown in Figure 2(g) and (h). Although chemical  
234 deposition and physical sputtering both have better step coverage with isotropic deposition, this  
235 will lead to the full coverage of the surface of the substrate. The deposition would happen not  
236 only on the top of the photoresists in the channels but also the sides, which prevents the  
237 photoresist from being washed away through the open sides. On the other hand, by leveraging  
238 the directional deposition of e-beam deposition with poor step coverage, the silicon will be only  
239 deposited onto the top of the photoresist, leaving the sides open to the air. Therefore, the  
240 photoresist can be washed away easily through the open sides. To ensure the thorough removal  
241 of the photoresist, the silicon layer should be better coated less than one fourth of the photoresist  
242 layer thickness, which is 1.3  $\mu\text{m}$ , to give more height difference between the photoresist layer  
243 and the silicon layer on the substrate. Thus, we chose to deposit 250 nm silicon layer. The  
244 photoresist patterned substrate was loaded in the E-beam evaporation chamber, which was  
245 pumped down to  $2\text{e}^{-6}$  Torr base pressure. The E-beam deposition is at an average rate of 1.6  $\text{\AA}/\text{s}$   
246 at temperatures 16 – 50 Celsius degree, thus it only takes no more than thirty minutes to reach  
247  $\sim 250$  nm for all loaded samples (20 per load with the sample dimension of 2 cm  $\times$  2 cm).

#### 248 **2.2.4. Lift-off process**

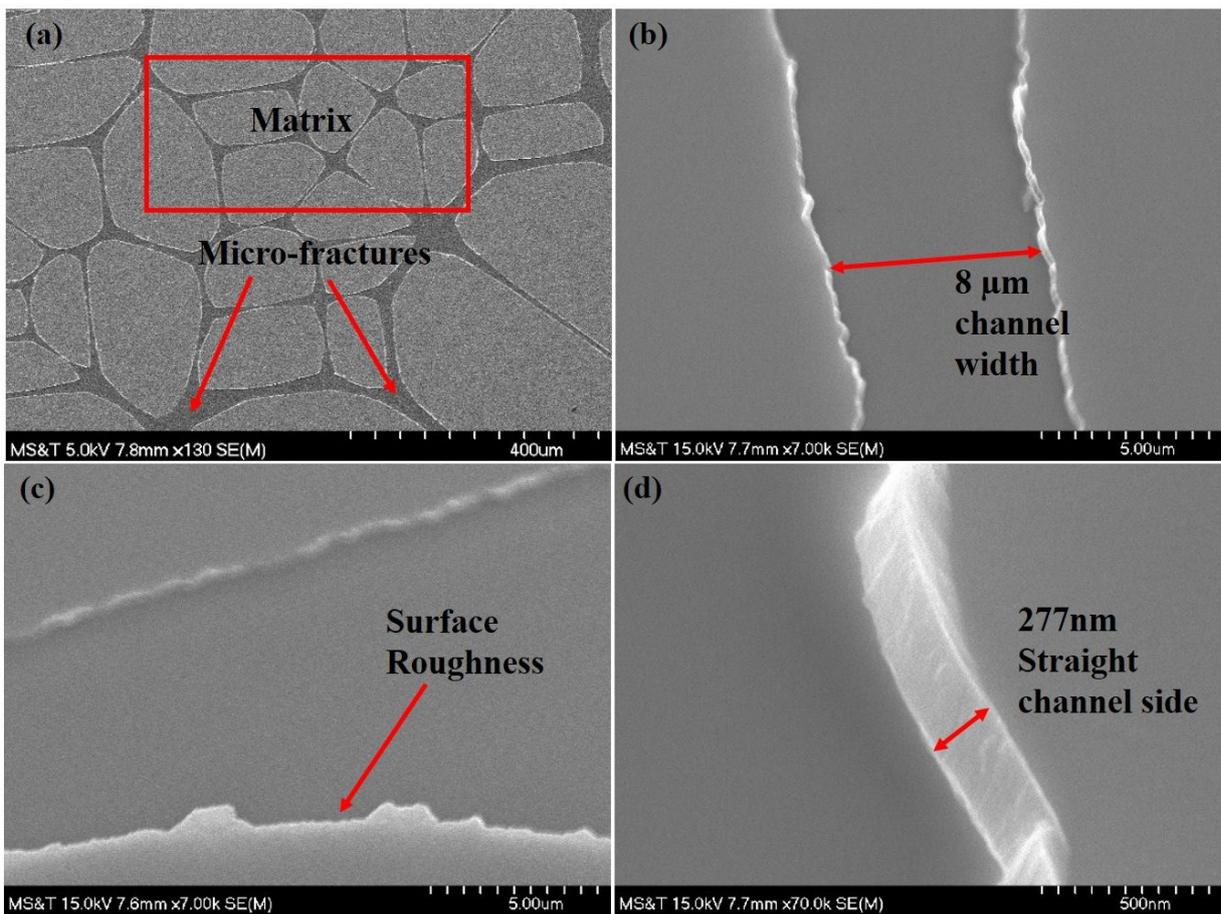
249 The lift-off process after thin film deposition has been used for decades in semiconductor  
250 and integrated circuit (IC) areas as a simple and quick method for patterning thin metal material  
251 films.<sup>55-57</sup> However, it has rarely been brought into microfluidic model fabrication field. We  
252 herein utilized direct lift-off process after the E-beam evaporation process to wash away the  
253 remaining photoresists in the channels. The substrate was first soaked in the Remover-PG  
254 solution and let it stand for 10 mins. Then, the ultrasonic cleaner with deionized water was used  
255 to clear out most of the photoresist preliminarily. Later, the substrate was cleaned intensively  
256 by immersing into the Piranha Solution (3:1  $\text{H}_2\text{SO}_4:\text{H}_2\text{O}_2$ ) for 20 mins to remove the photoresist  
257 residue and other contaminants. Finally, the substrate was rinsed by deionized water and blow-  
258 dried thoroughly. The lift-off process would peel off the photoresist with top-coated silicon

259 layers from the substrate completely, leaving the channels clean to give spaces for fluid flow.  
260 However, in some situations due to improper and incomplete dissolution of the photoresist, the  
261 retention problem would occur. The top coated silicon would adhere to the bottom silicon grain  
262 that should remain. To handle this problem, we conducted several lift-off processes with  
263 deposited silicon layers of different thickness from 100 nm to 500 nm with interval of 50 nm.  
264 It was not surprised that the thicker the deposited silicon layers, the more possible for retention  
265 problem occurs which causes more difficulties to wash away the photoresist. Either the side  
266 windows were too small to let the remover-PG flush completely or the silicon grains were  
267 peeled off together with the photoresist. The deposited material layer should not be thicker than  
268 two thirds of the photoresist to ensure a complete separation.<sup>58</sup> However, we found that it began  
269 to become difficult when the deposited silicon layer thickness is above 300 nm, which is about  
270 one fourth of the photoresist thickness (1.3  $\mu\text{m}$ ). It is also the nature of the positive photoresist  
271 that limits the height of the deposition layer. As shown in Figure 2(i) and (j), the undercut  
272 profiles are different between positive and negative photoresist with the silicon deposited on  
273 the top. They both have trapezoidal shapes after exposition. However, the undercut profile of  
274 positive resist is less advantageous than that of the negative photoresist whose inverted one has  
275 much bigger open access to the remover-PG solution. Although negative resist has been used  
276 mostly in lift-off process in microelectronic field, the higher cost and the difficult removal  
277 process still need to be considered. A diffuser by diverting the UV light can be utilized to change  
278 the positive photoresist undercut profile to the re-entrant profile for facilitating the lift-off  
279 process.<sup>59</sup> For our experiment, we did not use any other auxiliary method to ease the lift-off  
280 process since we seriously controlled the deposited silicon layer thickness below one fourth of  
281 the positive photoresist thickness to achieve a complete lift-off process.

### 282 ***2.2.5. Surface and Channel Characteristics***

283 After the lift-off process, the surface and the channel characteristics were analyzed. The  
284 thickness of the deposited silicon was measured using Sloan Dektak 3030 surface profiler

285 measuring system. The probe went 300  $\mu\text{m}$  across of two random grains and measured the  
286 channel depth between them. Inside the test area, the channel width is approximately 20  $\mu\text{m}$   
287 and the depth is about 277.7 nm. The surface is of good flatness, except for a few sharp peaks  
288 caused possibly by the dusts on the substrate surface. To demonstrate the profile of channel side  
289 wall, scanning electron microscopy (SEM) images of the model in tilt 45 degrees angle were  
290 taken using Hitachi S-4700 FESEM microscope as shown in Figure 3. Figure 3(a) shows the  
291 top overview of one part of the matrix and adjacent micro-fractures generated using Voronoi  
292 tessellation algorithm, which shows the matrix parts with smaller pore size while the micro-  
293 fractures with the larger pore size. Although the channel may have some degree of roughness  
294 due to the lift-off process, as shown in Figure 3(b) and (c), the channel side wall is shown to be  
295 vertical to the substrate as shown in Figure 3(d), which has better profile than wet etching.



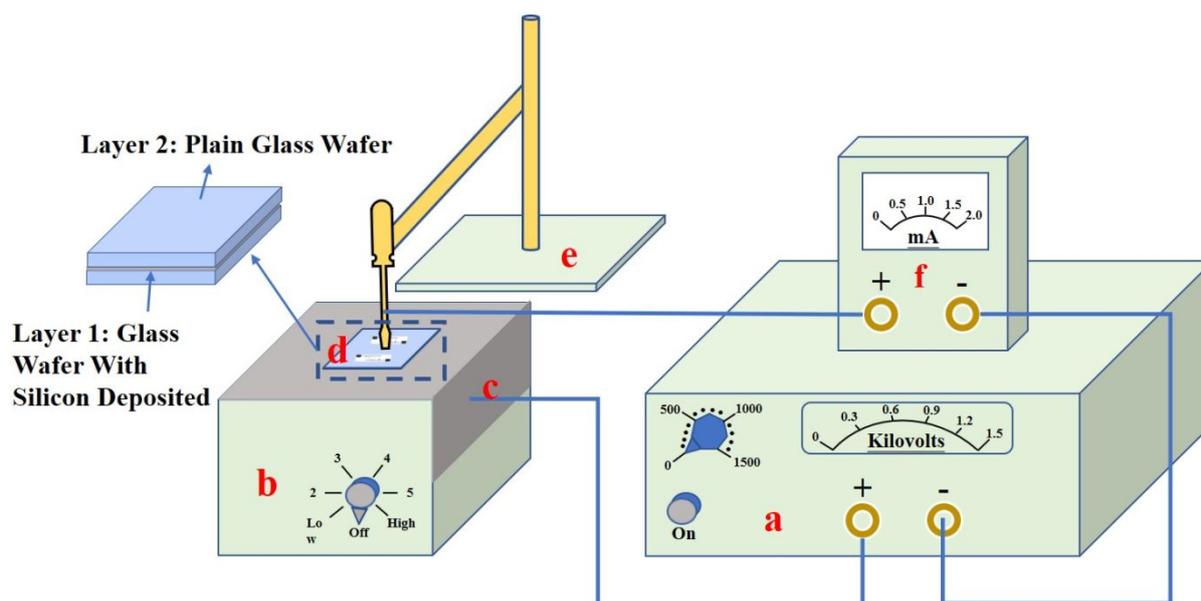
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297 Figure 3. SEM images of (a) matrixes and micro-fractures demonstration; (b) matrix channel  
298 with the width of 8  $\mu\text{m}$ ; (c) sidewall roughness; (d) straight channel wall profile with the depth  
299 of 277 nm.

### 300 **2.2.6. Anodic Bonding**

301 Anodic bonding can deliver strong bonding strength while keeping the substrate at low  
302 temperature.<sup>60</sup> Glass to glass anodic bonding can be realized by using silicon or other metal  
303 films as the intermediate layers and anodic bonding at no more than 400 Celsius degrees and  
304 700 Volts to make it possible for optical detection with fluorescence microscopy in biological  
305 and biomedical field, microfluidic systems where transparent walls were demanded.<sup>32, 61-63</sup> We  
306 used our self-assembly anodic bonding device to conduct the final anodic bonding process to  
307 seal the glass substrate with silicon layer and the plain glass cover hermetically. As shown in  
308 Figure 4, Our self-assembly anodic bonding device includes a HP Keysight 6515A high voltage  
309 DC power supply (0-1600V,5mA), a hot plate with an aluminum-foil paper covered, an  
310 ammeter and a probe stand with a metal probe fixed. An aluminum-foil paper was wrapped  
311 over the hot plate surface tightly as the conducting layer. The substrate with the silicon layer  
312 was placed first onto the aluminum as layer 1, followed with the placement of the cover glass  
313 onto the substrate as layer 2. Before placing, the substrate and the cover glass were already  
314 rinsed together in Piranha Solution (3:1  $\text{H}_2\text{SO}_4:\text{H}_2\text{O}_2$ ) for 20 mins after lift-off process to avoid  
315 bonding issue because of the residual contaminants. The SEM images also show there are not  
316 visible additive residues in the channels. In the meantime, they were both changed to have  
317 strong hydrophilicity. The conductive probe was adjusted vertically to press onto the cover  
318 glass to initially apply a force for a pre-bond. By connecting the anode to the aluminum-foil  
319 paper and cathode to the probe through the ammeter, the preparation for bonding was finished.  
320 We then switched on the hotplate and set the goal temperature to around 350 Celsius degrees  
321 and wait the substrate be pre-heated for 10 minutes. We used an infrared thermometer to  
322 measure the surface temperature. After the temperature was stable around 350 Celsius degrees,

323 we slowly increased the voltage to 1200V and check the ammeter at the same time. The  
324 ammeter was being an indicator whether there is a short circuit occurred when increasing the  
325 voltage. If the current is over 1 mA at any time during voltage incensement, the voltage should  
326 decrease to zero and check the electrodes connections. The bonding process using point cathode  
327 electrode contact method can be observed, spread radially outwards from the probe pinpoint.  
328 This radial propagation process also avoids air trapping between the interface of glass and  
329 silicon. However, the bonding process cannot be completed only by contacting one point due  
330 to the large area of the chip surfaces. Therefore, whenever the spread stopped, we moved the  
331 conductive probe to another point to continue the bonding process until all parts were bonded  
332 together. This point contact bonding method is much faster than the flat cathode electrode  
333 contact method and also costless.<sup>64</sup> It is also noteworthy that there were no collapsed channels  
334 found after the anodic bonding process. The channel aspect ratio (depth to width) has been  
335 demonstrated to be a crucial diameter when conducting a bonding process for either glass-  
336 silicon or glass-glass models.<sup>65</sup> For a glass cover anodic bonded onto a silicon substrate, due to  
337 the applied strong electrical force, the top and bottom surfaces would contact and seal the  
338 channel permanently if the aspect ratio is smaller than 0.004. For a fusion bonding process  
339 between two glass wafers, the high temperature would deform the glass material and thus cause  
340 the collapse of the channels if the aspect ratio is smaller than 0.0005. For our anodic bonding  
341 process under low temperature, there are also no strong electrical interactions between the top  
342 and bottom glass wafers. Therefore, the channels were all survived with the aspect ratio even  
343 smaller than 0.0005.(e.g. conduits and the vugs).



344  
 345 Figure 4. Schematic of the lab-based anodic bonding apparatus. a. high voltage DC power  
 346 suppl (0-1600V,5mA); b. hot plate; c. aluminum paper; d. two glass wafers with an  
 347 intermediate silicon layer; e. probe stand; f. amperemeter;

### 348 **3. Experimental verification for the glass-silicon micromodel**

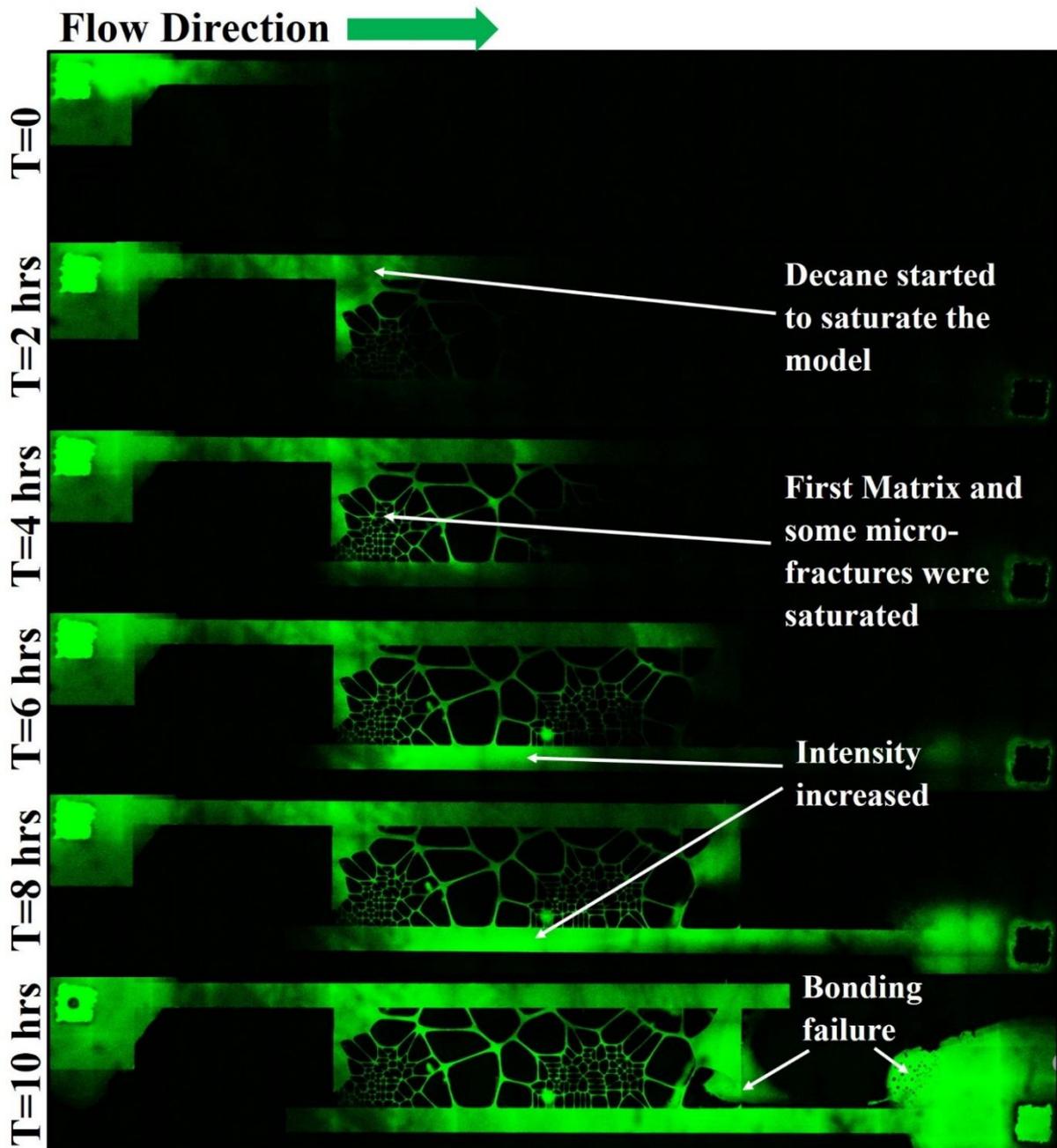
349 We tested the practicability of the glass-silicon-glass micromodel by conducting a two-  
 350 phase fluid displacement experiment. Deionized water (DI water) was used as the wetting phase  
 351 and decane as the non-wetting phase. The fluid flow process was investigated by utilizing  
 352 confocal laser scanning microscopy (CLSM). To distinguish the two kinds of fluids under  
 353 different lasers, they were both fluorescent-dyed using Alexa Flour 594 for the water phase and  
 354 Nile Red for the oil phase (both from Sigma-Aldrich), respectively. The DI water was in red  
 355 and the decane was in green after separately excited by lasers at 488 nm and 561 nm. The  
 356 micromodel was firstly saturated with the decane injected by using syringe pump (Harvard  
 357 Apparatus, model 88-3015). Then the decane was displaced by the DI water at the flow rate of  
 358 0.02 mL/hr. Because it is a large field micromodel, even if we used 10 X objective lens that  
 359 have the biggest vision of field among all lenses, we can only observe partial areas. Therefore,  
 360 the stage was set moved automatically from left corner inlet to the right corner outlet with 19  
 361 horizontal steps and 5 vertical steps. All fields were then stitched together to obtain a whole

362 image which covers all parts of the model. We scanned and recorded the whole injecting process  
363 using resonant scanning mirrors instead of traditional galvanometer mirrors to acquire high  
364 scanning speed. Although the resolution became worse, the scanning speed can be up to 7.7  
365 frame per second and it takes only 40 seconds to scan the whole model. All experiments were  
366 conducted at room temperature.

### 367 **3.1. Oil Saturation Process**

368 In this research, since our focus is to fabricate the model and verify its usability to conduct  
369 a flooding experiment, we did not consider the irreducible water saturation to mimic the real  
370 reservoir saturation history as it is neglectable for verifying the usability of this model.  
371 Therefore, we only did the water flooding imbibition test by directly saturating the model with  
372 oil first. Decane (0.92 cP at 20°C) was injected using 1/16-inch inner diameter tubing into the  
373 inlet nanoport (IDEX Health & Science LLC) at flow rate of 0.02mL/L. As shown in Figure 5,  
374 it took about 10 hours to fully saturate the microfluidic model with decane phase. The flow  
375 direction was from top left corner inlet to the bottom right outlet where was always open to the  
376 air with no backpressure added. From the time sequence from top to the bottom with the time  
377 interval of 2 hours, we can observe that the intensity of fluorescent was increased with the  
378 gradually saturation of the oil phase. From  $T = 4$  hrs, the flow started to flow into the bottom  
379 conduit, mostly from the middle micro-fractures other than the matrix at left, which verifies the  
380 assumption for the interface conditions in to govern the coupled flow in a dual-porosity media  
381 and its adjacent conduits<sup>66</sup>. At  $T = 6$  hrs, the bottom conduit has more fluid flown into than the  
382 matrix at right. Until the end of the injection, except for the left corner of the bottom conduit,  
383 all the top and bottom conduits were saturated, together with the two matrixes and micro-  
384 fractures. The bonding failure may occur at the edges of the inlet and outlet, as well as some  
385 edges at the matrix boundaries as indicated in Figure 5 ( $T = 10$  hrs). The partial bonding failure  
386 would not affect the general trend of the fluid flow inside the porous media seriously. We did

387 not observe any leakage from the chip until the injecting pressure was higher than 420 Psi when  
 388 the solidified epoxy that fixed the nanoport on the chip started to crack and leak but not for  
 389 other parts of the model. However, our injecting pressure was no more than 200 Psi so there  
 390 was no leakage observed throughout the experiments. The water phase was then ready to be  
 391 injected until there was no fluorescent intensity increase observed which means the porous  
 392 media was fully saturated with the decane oil phase.



393

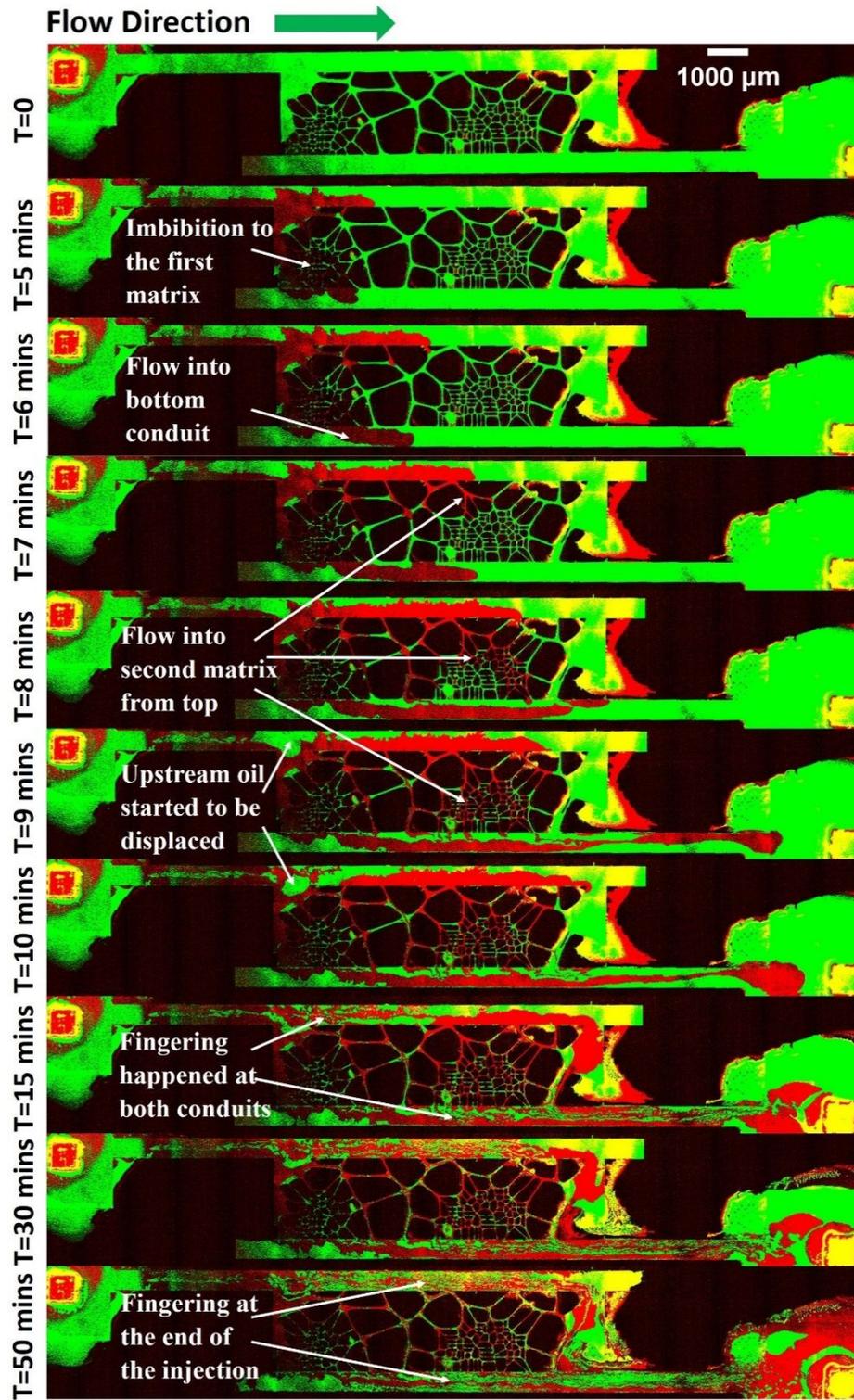
394 Figure 5. Oil saturation process in a time sequence (top to bottom) with flow direction (left to  
395 right).

### 396 **3.2. Forced water imbibition process**

397 We conducted the water imbibition processes in two directions with constant flow rate of  
398 0.02mL/hr. One is positive injection from the inlet, another one is reverse injection from the  
399 outlet. The two matrixes were adjacent to the bottom conduit when the water was forwardly  
400 injected into the micromodel, while adjacent to the top conduit when the water was reversely  
401 injected. The decane oil phase and water phase were in true excitation color of green and red.  
402 Both two imbibition processes were successful with no leakage found and stopped at about fifty  
403 minutes when no more significant phase changes after water breakthrough within the models.

404 Because of the strong hydrophilicity of glass and silicon layer after rinsed in piranha  
405 solution before bonding, and with the very low flow rate, the water intended to be imbibed into  
406 the matrixes first other than micro-fractures from top conduit. For the forward injection process  
407 as shown in Figure 6, the water started to invade into the top conduit and imbibed into the first  
408 matrix at the same time at around 5 minutes from the imbibition beginning. The waterflow then  
409 branched into two different directions. One branch continued to flow in the conduit and another  
410 branch flew into the bottom conduit. Although some of the water in the matrix flew into the  
411 middle micro-fractures, quicker flow velocity was found at top and bottom conduits.  
412 Consequently, at  $T=8$  minutes, the water from the top conduit was imbibed into the second  
413 matrix and started to displace the oil into the bottom conduit forced by the backpressure of  
414 water behind it. Since the decane oil is less viscous than the water, a fingering phenomenon  
415 was observed as the oil flow had a finger-like structure as it travelled towards the outlet while  
416 remained connected. Besides, as the pressure built up within the whole model, part of the  
417 remaining oil at upstream conduit was also started to be displaced and also acted finger-like  
418 when it met the water that has already been in the top conduit as shown at  $T=10$  and 15 minutes.

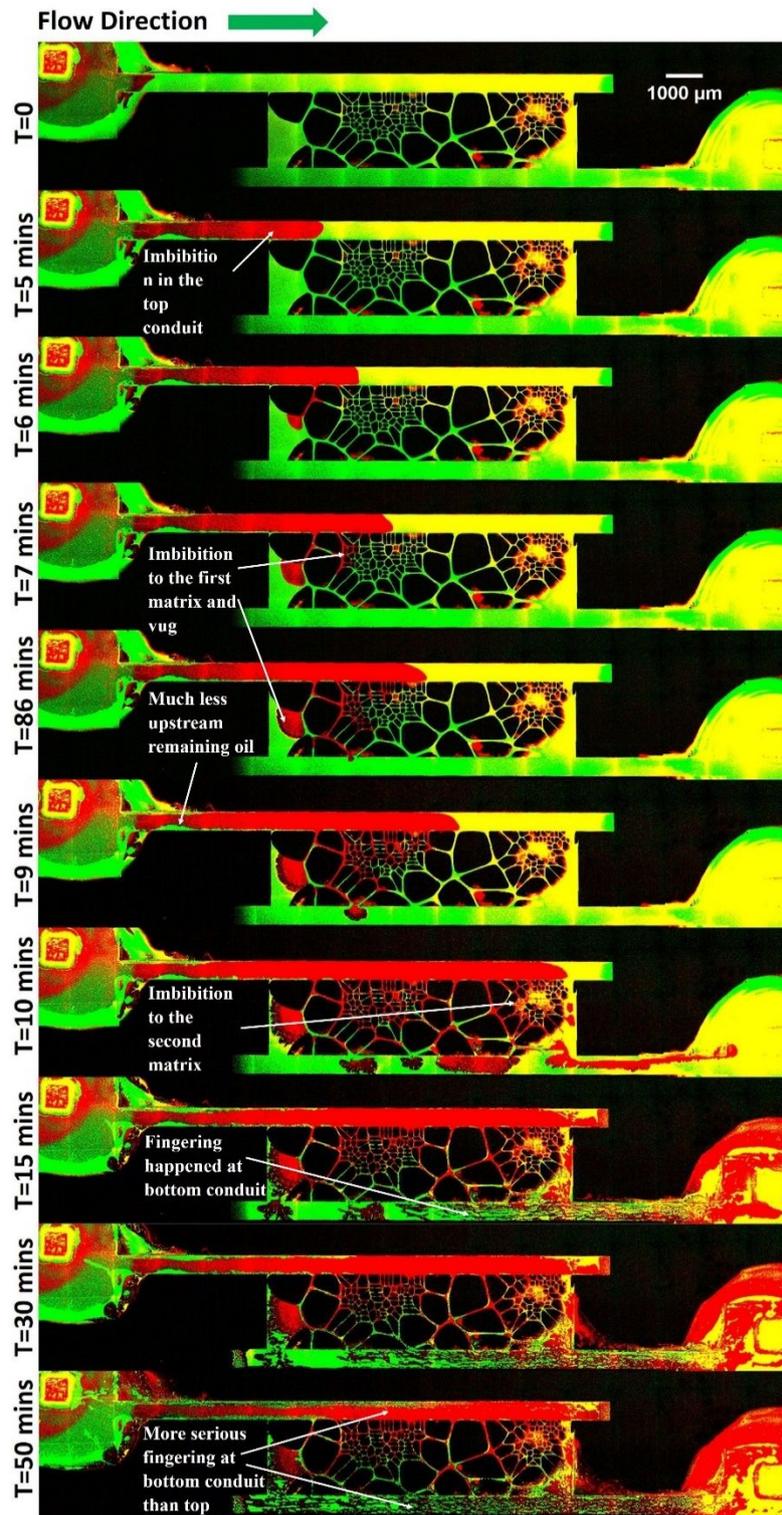
419 The fingering became more remarkable at  $T=30$  minutes at both conduits and some of the  
420 matrixes and micro-fractures were re-saturated by some upstream remaining oil. From  $T=30$   
421 minutes to  $T=50$  minutes, there were no other significant changes, but some connected finger-  
422 like oil was stretched longer or disconnected into dispersed oil droplets by the continuously  
423 water flooding. The fingering phenomenon was also found in the reverse injection process.  
424 However, it happened mostly only in the bottom conduit while only rare were found in the top  
425 conduit as shown in Figure 7. At the beginning, the water flow uniformly into the top conduit  
426 with much less remaining oil left at upstream conduit. The water reached the first matrix on the  
427 top at  $T=6$  to  $T=8$  minutes and imbibed into it. Meanwhile, some water was also diverted  
428 towards the left-side vug. At  $T=9$  minutes, the water in the first matrix started to flow into the  
429 bottom conduit and continued to flow right to the middle micro-fractures afterwards. As the  
430 water in the top conduit insisted to reach the second matrix at the top right corner, the water in  
431 the micro-fractures firstly flew into the bottom conduit and converge with water from the  
432 second matrix later at  $T=10$  minutes. The fingering occurred in the bottom conduit at  $T=15$   
433 minutes as the upstream remaining oil in the bottom conduit was displaced towards the outlet  
434 and became the most serious at  $T=50$  minutes. Although there was also some fingering observed  
435 at the boundaries of the top conduit, it was much less significant than that of the scenario in  
436 which the water was forwardly injected. The hypothesized reason is that, when the water was  
437 forwardly injected, the two matrixes were much closer to the inlet, which may generate a strong  
438 imbibition area for the water at the very beginning of the flooding process. On the contrast, the  
439 two matrixes were adjacent to the top conduit and farther to the inlet. Therefore, the water  
440 would not prefer to flow into the micro-fracture at the beginning, but rather to flow steadily in  
441 the top conduit until reached the first matrix. Thus, there were much less remaining oil left at  
442 the upstream since most of them were already been displaced through the top conduit. As a  
443 result, the fingering was not likely to be found in the top conduit for the reverse injection  
444 scenario, which in return leads to a higher oil recovery.



445

446 Figure 6. Water imbibition process in a time sequence (top to bottom) with flow direction (left

447 to right).



448

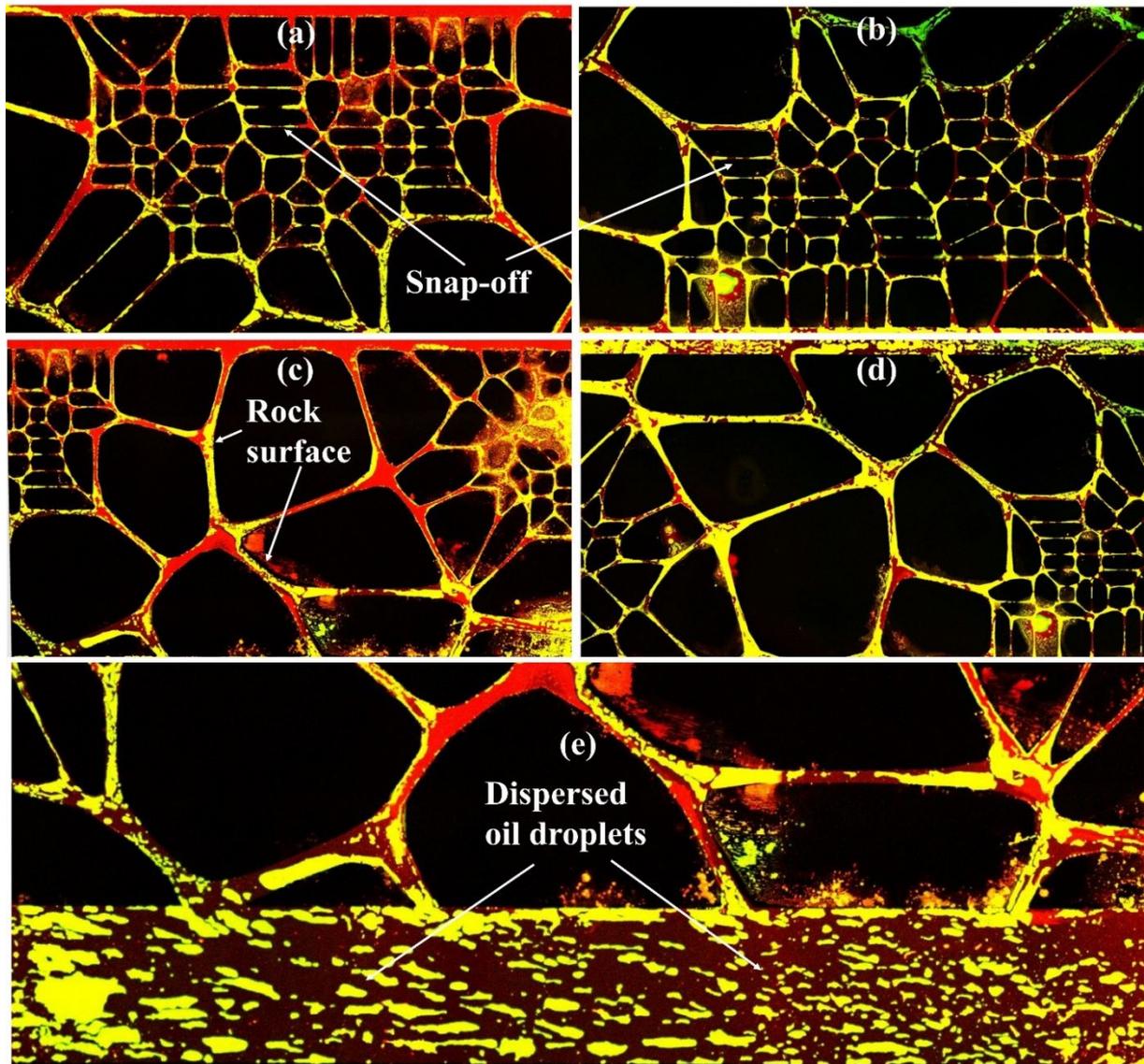
449 Figure 7. Reverse water imbibition process in a time sequence (top to bottom) with flow  
 450 direction (left to right).

451

452

### 453 **3.3. Residual oil distribution comparison**

454       The residual oil is the oil that cannot be recovered by simple conventional water flooding  
455 method. We repeated the experiments in other two models built with the same method and still  
456 found the residual oil was much less when the two matrixes were adjacent to the top conduit  
457 than that of the case in which the two matrixes were adjacent to the bottom conduit. For both  
458 cases, the residual oil would exist in different forms within the matrixes as shown in Figure 8(a)  
459 and (b) and the microfractures as shown in Figure 8(c) and (d). Some of them were adhered to  
460 the rough surface and cannot be displaced by the water while most of them left in the middle of  
461 the channel in different shapes. Besides, snap-off was also observed at very thin matrix channel,  
462 resulting in slugs of oil droplet trapped in the pore throat with water phase filled among them.  
463 It was also found that the re-saturated oil can be hardly driven by following water flooding  
464 process when the two matrixes were adjacent to the bottom conduit, which causes much more  
465 residual oil as shown in Figure 8(b) and (d) than that of reverse injection case as shown in  
466 Figure 8(a) and (c). However, the residual oil distributed similarly in the bottom conduit for  
467 both cases, as the finger-structured oil plumes were destroyed by constantly water flooding and  
468 randomly dispersed with the direction pointing to the outlet.



469

470 Figure 8. Residual oil distribution conditions comparisons in matrixes, micro-fractures of two

471 different geometries (a) and (c) top conduit with adjacent matrixes; (b) and (d) bottom conduit

472 with adjacent matrixes; (e) bottom conduit.

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### 478 **3. Conclusion and future work**

479 We successfully used e-beam physical evaporation deposition, lift-off process and  
480 anodic bonding method to fabricate a fully transparent, shale-like dual-porosity glass-silicon-  
481 glass micro-nonfluidic model in a simple, fast and low-cost way. The fabrication process gets  
482 rid of the time-consuming and complicated etching method while still generates complex  
483 porous media network with uniform channels in a much shorter time. To verify the functionally  
484 and practicability of the model, two phase fluid flow displacement experiments with two  
485 injection modes were conducted separately and visualized using confocal laser scanning  
486 microscope. Owing to the large width-to-depth ratio range (12-2000) of the model, especially  
487 for two conduits at top and bottom, the fingering phenomena that may happen in a Hele-Shaw  
488 cell were brought into sight. Moreover, we observed that it is possible the fingering problem  
489 could exist when displacing phase viscosity is higher than that of the displaced phase due to the  
490 geometry of the porous media. Besides, the residual oil distributed as different forms in the  
491 matrixes, micro-fractures and conduits. Snap-offed oil droplets trapped in thin channel pore  
492 throat, oil chains left in the wider matrix channels, boundary-adhered oil films due to the surface  
493 roughness, and the dispersed oil droplets in the conduits were found, respectively. By changing  
494 the flow pattern by shifting two matrixes adjacent to the bottom and then top conduits, we  
495 demonstrated that different matrix/micro-fracture/macro-fracture interlacing geometries that  
496 may affect flow patterns, which would affect the oil recovery seriously for dual-porosity  
497 heterogeneous shale porous media.

498 Although this micro-/nanofluidic model provides with a quick and simple platform for  
499 direct visualizing the fluid flow dynamically in a dual-scale porous media, there are still further  
500 expectations for the future work. The micro-/nanofluidic model can be improved by designing  
501 more different patterns that representing more complicated reservoir conditions. The limitation  
502 of depth-to-width aspect ratio by using glass-glass anodic bonding method still needs further

503 investigated, which would provide the possibility of fabricating the micromodel even at sub-10  
504 nm scale. The residual oil distribution, flow velocity, pressure difference and fingering problem  
505 are still need further researched quantitatively and systematically to get a comprehensive  
506 understanding of the fluid flow within dual-scale micro-/nano channels at pore level.

507

## 508 **Author contributions**

509 Y. Zhang designed and fabricated the microfluidic chips, implemented experiments, and  
510 prepared the original manuscript. C. Zhou offered the use of photolithography equipment and  
511 materials, gave guidance and suggestions to lift-off process. C. Qu offered the use of the E-  
512 beam evaporator and deposition materials, gave guidance and suggestions to E-beam  
513 evaporation deposition process. B.Bai is the principle supervisor and advisor of this research.  
514 M. Wei and X. He are the co-supervisors and co-advisors of this research. All supervisors  
515 proposed the conceptualization of this research and provided the funding support. All authors  
516 had discussions with the results and contributed to manuscript correction and proofread.

517

## 518 **Conflict of Interest**

519 The authors declare no conflict of interest.

## 520 **Acknowledgement**

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# Fabrication and Verification of a Glass-Silicon-Glass Micro-/nanofluidic Model for Investigating Multi-phase Flow in Shale-like Unconventional Dual-Porosity Tight Porous Media

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Time efficient and costless lift-off process combined with anodic bonding method was used to create a 'shale-like' glass-silicon-glass microfluidic model.

